

Received
Sept 26 1995
Group 1507

Case 2 68520 1507

RESPONSE UNDER 37C.F.R. 1.116
-EXPEDITED PROCEDURE-
EXAMINING GROUP 1507



In the United States Patent and Trademark Office

In re Application of:

Group Art Unit: 1507

Neil F. Haley, et al

Examiner: L. Weiner

RADIATION-SENSITIVE
COMPOSITION CONTAINING A
RESOLE RESIN, A NOVOLAC
RESIN, AN INFRARED ABSORB-
ER AND A TRIAZINE AND USE
THEREOF IN LITHOGRAPHIC
PRINTING PLATES

I hereby certify that this correspondence is being
deposited TODAY with the United States Postal Service
as first class mail in an envelope addressed to
Assistant Commissioner For Patents, Washington, D.C.
20231.

Alfred P. Lorenzo
Name

Signature

22,503
Reg. No.

AUGUST 21, 1995
Date of Signature

Serial No. 212,434

Filed 14 March 1994

Honorable Assistant Commissioner For Patents
Washington, D.C. 20231

Sir:

AMENDMENT AFTER FINAL REJECTION

In response to the Office Action of August 7,
1995, please amend the above-identified application as
follows:

In the Claims:

Please amend claim 1 as follows:

1. (Amended) A radiation-sensitive
composition useful for the preparation of an imaging
layer of a lithographic printing plate that is
sensitive to both ultraviolet and infrared radiation
and capable of functioning in either a positive-working
or negative-working manner; said radiation-sensitive
composition comprising (1) a resole resin, (2) a
novolac resin, (3) a haloalkyl-substituted S-triazine,
and (4) an infrared absorber in amounts such that the
solubility of said imaging layer in aqueous alkaline
developing solution is reduced in exposed areas and
increased in unexposed areas by the steps of imagewise
exposure to activating radiation and heating.

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